IAP10 Rec'd PCT/PTO 22 NOV 2005

NATIONAL PHASE UTILITY APPLICATION

Transmittal to the (DO/EO/US) Under 35 USC 371 Attorney Docket No.: SHIGA7.033AP 10./557694

Int'l Application No.: PCT/JP2004/008004

Int'l Filing Date: June 2, 2004 Priority Date Claimed: June 5, 2003

Title: RESIN FOR PHOTORESIST COMPOSITION,

PHOTORESIST COMPOSITION AND METHOD FOR

FORMING RESIST PATTERN
Express Mail Label No.: EV718233132US

Direct all correspondence to Customer No.: 20995

Date: November 22, 2005

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United States Patent and Trademark Office P.O. Box 1450 Alexandria VA 22313-1450

The following enclosures are transmitted herewith to be filed in the patent application of:

Inventors:

1. Hideo Hada

2. Masaru Takeshita

3. Shogo Matsumaru

4. Hiroaki Shimizu

APPLICATION ELEMENTS:

- (X) This is a FIRST submission of items concerning a filing under 35 U.S.C. § 371.
- (X) A copy of the International Application as filed (35 U.S.C. § 371(c)(2)) has been communicated by the International Bureau.
 - (X) PCT/IB/308 enclosed.
- (X) An English translation of the International Application as filed is attached hereto.
- (X) Amendments to the claims of the International Application under PCT Article 19 (35 U.S.C. § 371(c)(3)) have not been and will not be made.
- (X) An Oath or Declaration signed by the inventors (35 U.S.C. § 371(c)(4)).

OTHER APPLICATION PARTS:

- (X) Preliminary Amendment in 7 pages.
- (X) Application Data Sheet in 4 pages.
- (X) Recordation form cover sheet and Assignment in 3 total pages (cover sheet & assignment).
- (X) An Information Disclosure Statement and PTO/SB/08 equivalent listing references for consideration:
 - (X) Listing 18 references.
 - (X) Enclosing 14 references.
- (X) Cover page of PCT publication WO 2004/108780.
- (X) International Search Report (PCT/ISA/210).

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NATIONAL PHASE UTILITY APPLICATION

Transmittal to the (DO/EO/US) Under 35 USC 371 Attorney Docket No.: SHIGA7.033APC

First Named Inventor: Hideo Hada

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(X) Written Opinion (PCT/ISA/237).

(X) Return prepaid postcard.

FILING FEES:

	FEE CALCULA	TION					
FEE TYPE & DETERMINATION		LARGE FEE	CALCULATION		TOTAL		
Basic Filing Fee under 1.492(a)		1631 (\$300)				\$300	
Search Fee under 1.492(b) (enter one in TOTAL column)						
(1) USPTO was ISA (4)	1640 (\$0)				\$400		
(2) USPTO was the	1641 (\$100)						
(3) Foreign Search I	1642 (\$400)						
(4) No Search Repo	rt Enclosed	1632 (\$500)					
Examination Fee under 1.492(c) (enter one in TOTAL column)							
(1) USPTO was ISA/IPE.	1643 (\$0)				\$200		
(2) Non US IPEA or Non	1633 (\$200)						
Excess Claims	17 - 20 = 0	1615 (\$50)	0	x	50 =	\$0	
Excess Ind. Claims	2 - 3 = 0	1614 (\$200)	0	х	200 =	\$0	
Multiple Dep. Claim		1616 (\$360)				\$0	
Application Size Fee	0 - 100 = 0	1681 (\$250)	0	x	250 =	\$0	
Late English Translation		1618 (\$130)		•.		\$0	
Assignment		8021 (\$40)	1	х	40 =	\$40	
		TOTAL FEE DUE			\$940		
	TOTAL F	EE PAID (If Diffe	erent 7	han l	Fee Due)	\$	

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The Commissioner is hereby authorized to charge any additional fees which may be required, now or in the future, or credit any overpayment to Account No. 11-1410.

Daniel E. Altman

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CERTIFICATE OF MAILING BY "EXPRESS MAIL"

Attorney Docket No.

SHIGA7.033APC

Applicant(s)

Hada et al.

For

RESIN FOR PHOTORESIST COMPOSITION,

PHOTORESIST

COMPOSITION AND

FORMING

RESIST

METHOD PATTERN

Attorney

: Daniel E. Altman

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FOR

Date of Deposit

November 22, 2005

I hereby certify that the accompanying

Transmittal letter; English translation of specification in 48 pages; Preliminary Amendment in 7 pages; Application Data Sheet in 4 pages; Declaration/Power of Attorney in 2 pages; Recordation Form Cover Sheet and Assignment in 3 pages; International Search Report and Written Opinion; PTO/IB/308; cover page of PCT publication; Information Disclosure Statement, PTO Form PTO/SB/08 Equivalent with 14 references; Check for Filing Fee; Return Prepaid Postcard

are being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and are addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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